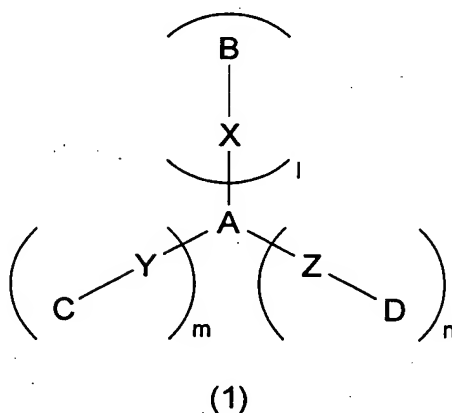


ABSTRACT

A photoresist base material comprising an extreme
ultra-violet reactive organic compound of the following
5 formula (1),



wherein A is a central structure that is an
10 aliphatic group having 1 to 50 carbon atoms, an aromatic
group having 6 to 50 carbon atoms, an organic group
containing these together or an organic group having a
cyclic structure formed by repetition of these, each of B
to D is an extreme ultra-violet reactive group, a group
15 having reactivity to the action of a chromophore active to
extreme ultra-violet, or a C₁ to C₅₀ aliphatic group, C₆ to
C₅₀ aromatic group, an organic group containing these
together or a substituent having a branched structure,
containing such a reactive group, X to Z are single bonds
20 or ether bonds, 1 to n are integers of 0 to 5 satisfying 1
+ m + n ≥ 1, and A to D may contain a substituent having a
heteroatom. The photoresist base material and a composition
thereof enable ultrafine processing based on extreme ultra-

violet.